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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/829,141	04/21/2004	James C. Kim	LUM-03-06-06	5434
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PATENT L	AW GROUP LLP	NGUYEN, JOSEPH H		
2000 1101111	2635 NORTH FIRST STREET		ART UNIT	PAPER NUMBER
SUITE 223 SAN JOSE,	A 95134		2815	
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Please find below and/or attached an Office communication concerning this application or proceeding.

	<u> </u>	Application No.	Applicant(s)			
		10/829,141	KIM ET AL.			
	Office Action Summary	Examiner	Art Unit			
	·	Joseph Nguyen	2815			
Period fo	The MAILING DATE of this communication app or Reply	pears on the cover sheet with the c	orrespondence address			
WHIC - Exter after - If NO - Failu Any r	ORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DATE of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. Period for reply is specified above, the maximum statutory period ver to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be timwill apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nely filed the mailing date of this communication. D (35 U.S.C. § 133).			
Status	·					
1)⊠ 2a)⊠ 3)□	Responsive to communication(s) filed on <u>12 Jac</u> This action is FINAL . 2b) This Since this application is in condition for alloward closed in accordance with the practice under E	s action is non-final. nce except for formal matters, pro				
Dienociti	ion of Claims	•				
5)□ 6)⊠ 7)⊠	4) Claim(s) 1-23 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) Claim(s) is/are allowed. 6) Claim(s) 1-5 and 7-23 is/are rejected. 7) Claim(s) 6 is/are objected to. 8) Claim(s) are subject to restriction and/or election requirement.					
Applicati	ion Papers					
	The specification is objected to by the Examine	er.				
10)⊠ The drawing(s) filed on <u>21 April 2004</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.						
,—	Applicant may not request that any objection to the	•				
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11)	The oath or declaration is objected to by the Ex	xaminer. Note the attached Office	Action or form PTO-152.			
Priority (ınder 35 U.S.C. § 119	•				
a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Burea See the attached detailed Office action for a list	ts have been received. ts have been received in Applicati nity documents have been receive u (PCT Rule 17.2(a)).	ion No ed in this National Stage			
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Attachment(s) 1) Notice of References Cited (PTO-892) 4) Interview Summary (PTO-413)						
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 5) Notice of Informal Patent Application (PTO-152) Other:						

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DETAILED ACTION

Claim Objections

Claim 1 is objected to because of the following informalities:

In claim 1, line 3, the word "wurtzite" should be corrected to read, "wurtzite crystal structure".

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 1-5, 15, 18-19 and 22-23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hata et al. (US 2003/0057434 A1) in view of Sun et al. ("Polarization anisotropy of the photoluminescence of M-plane).

Regarding claim 1, Hata et al. disclose in figure 4 a semiconductor light emitting device comprising a light emitting layer 5A (para [0079], line 2) disposed between an n type region 4 (para [0078], line 8) and a p type region 6 (para [0080], line 2) wherein the light emitting layer is wurzite (para [0119]) and the light emitting layer has a thickness greater tan 25A (para [009]). Note that the device-constituting layer comprising the light-emitting layer is a wurzite structure, and therefore the light-emitting layer is also wurzite. Hata et al. does not disclose a <0001> axis being substantially parallel to a top surface

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of the light-emitting layer. Applicant teaches in para [0011] the light emitting layer that has a top surface substantially parallel to <0001> axis is <1120> layer. Sun et al. teaches in page 3850, right column, lines 9-17 the light emitting layer is <1120> layer. Therefore, Sun et al. discloses a <0001> axis being substantially parallel to a top surface of the light-emitting layer. In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Hata et al. by having a <0001> axis being substantially parallel to a top surface of the light emitting layer to increase the polarization degree in a light emitting layer (page 3850, right column, line 1-2).

Regarding claims 2-4, Hata et al. discloses in para [0079], lines 2-7 the light-emitting layer has a thickness greater than 50A, 90A and 150A. Note that Hata et al. discloses the light emitting layer 5A has a plurality of barrier layers and well layers, each having a thickness of 5nm (50A). Therefore, the total thickness of the light-emitting layer is greater than 50A, 90A and 150A.

Regarding claim 5, Sun et al. discloses the light-emitting layer comprises <1120>.

Regarding claim 15, Hata et al. discloses in para [0079] the light emitting layer 5A is a first quantum well and further comprises a second quantum well and a barrier layer disposed between the first and second quantum well; wherein the first quantum well, second quantum well and barrier form an active region.

Regarding claim 18, Hata et al. discloses in figure 4 the active region 5A is disposed between first and second cladding layers 4, 6.

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Regarding claim 19, it is inherent the bandgap of the first and second cladding layers is larger than that of the first and second quantum wells so that holes and electrons can recombine in the active region and emit light.

Regarding claims 22-23, the light emitting device of Hata et al. and Sun et al. comprise a similar structure as that of the claimed light emitting device and therefore is capable of performing as claimed.

Claim 7 is rejected under 35 U.S.C. 103(a) as being unpatentable over Hata et al. and Sun et al., and further in view of Goetz et al. (US 2002/0171092 A1).

Regarding claim 7, Hata et al. and Sun et al. disclose the light emitting layer 5A comprising GaInN (para [0079], lines 2-7), not AllnGaN as claimed. However, Goetz et al. discloses the light-emitting layer can be formed of GalnN or AllnGaN (para [0022], lines 3-6). In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Hata et al. and Sun et al. by having the light emitting layer comprising AllnGaN because GalnN and AllnGaN are recognized in the art as equivalents.

Claims 8-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hata et al. and Sun et al., and further in view of Ibbetson et al. (US 6,515,313).

Regarding claim 8, Hata et al. and Sun et al. disclose substantially all the structure set forth in the claimed invention except the light emitting layer being graded from a first indium composition in a first portion of the light emitting layer proximate the n

type region to a second indium composition in a second portion of the light emitting layer proximate the p type region. However, Ibbetson et al. discloses in (col. 10, lines 31-43) the light emitting layer being graded from a first indium composition in a first portion of the light emitting layer proximate the n type region to a second indium composition in a second portion of the light emitting layer proximate the p type region. In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Hata et al. and Sun et al. by having the light emitting layer being graded from a first indium composition in a first portion of the light emitting layer proximate the n type region to a second indium composition in a second portion of the light emitting layer proximate the p type region to increase emission efficiency (col. 10, line 45).

Regarding claims 9-10, It would have been obvious to one having ordinary skill in the art at the time of the invention was made to modify Hata et al. and Sun et al. and Ibbetson et al. by having the first composition greater (claim 9) or less (claim 10) than the second composition, since it has been held that discovering an optimum value of a result effective variable involves only routine skill in the art. In re Boesch, 617 F.2d 272, 205 USPQ 215 (CCPA 1980).

Claims 11-14 and 16-17 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hata et al. and Sun et al., and further in view of Bour et al.

Regarding claims 11 and 12, Hata et al. and Sun et al. disclose substantially all the structure set forth in the claimed invention except the light emitting layer being

graded from a first aluminum composition in a first portion of the light emitting layer proximate the n type region to a second aluminum composition in a second portion of the light emitting layer proximate the p type region. However, Bour et al. discloses in para [0046] the light emitting layer being graded from a first aluminum composition in a first portion of the light emitting layer proximate the n type region to a second aluminum composition in a second portion of the light emitting layer proximate the p type region. In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Hata et al. and Sun et al. by having the light emitting layer being graded from a first aluminum composition in a first portion of the light emitting layer proximate the n type region to a second aluminum composition in a second portion of the light emitting layer proximate the p type region to improve the light output of the active region in light emitting device (para [0001], Bour et al.).

Regarding claims 13-14, It would have been obvious to one having ordinary skill in the art at the time of the invention was made to modify Hata et al. and Sun et al. by having the first composition greater (claim 13) or less (claim 14) than the second composition, since it has been held that discovering an optimum value of a result effective variable involves only routine skill in the art. In re Boesch, 617 F.2d 272, 205 USPQ 215 (CCPA 1980).

Regarding claim 16, Hata et al. and Sun et al. disclose substantially all the structure set forth in the claimed invention except an indium composition in one of the first and second quantum wells being graded. However, Bour et al. discloses in para [0027] an indium composition in one of the first and second quantum wells being

graded. In view of such teaching, it would have been obvious to one of ordinary skill in the art at the time the invention was made to modify Hata et al. and Sun et al. by having an indium composition in one of the first and second quantum wells being graded to improve the light output of the active region in light emitting device (para [0001], Bour et al.).

Regarding claim 17, Bour et al. discloses in para [0011] the barrier layer has a graded composition.

Allowable Subject Matter

Claim 6 is objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The following is a statement of reasons for the indication of allowable subject matter: The reference (s) of record do not teach or suggest, either singularly or in combination at least the limitation of "the light emitting layer comprises {101⁻0}" for claim 6.

Response to Arguments

Applicant's arguments filed on 01/12/2006 have been fully considered but they are not persuasive.

With respect to claim 1, applicant argues there is no explanation why increasing "the polarization degree in the light emitting layer" motivates a person of skill in the art to

combine Hata et al. with Sun et al. However, it is well known in the art increasing the polarization degree in the light emitting layer would obtain excellent brightness (See col. 9, lines 10-12 of Kaneko US 6,504,588 provided herein as evidence only). Also, Sun et al. teaches in the left column of page 3850 growing the III-nitride layer substantially parallel to <0001> axis would result in improved lasing performance. As such, there is a motivation to combine Hata et al. and Sun et al. Further, applicant argues growth of some of the layers in Hata et al's device along Sun et al's uncommon growth direction may result in a device with more defects. However, this is a mere allegation unsupported by evidence. Unless applicant can provide evidence to support this conclusion, the combination of Hata et al. and Sun et al. results in a better performing light emitting device as stated above. Lastly, applicant argues any III-nitride layer grown over Hata et al's non-single crystalline layer would revert to growing along the c-axis and would not grow as Sun et al's structure which is grown along an axis perpendicular to the c-axis, and thus the combination of Hata et al. and Sun et al. cannot be successful. However, this is again a mere allegation and speculation unsupported by evidence. Therefore, the combination of Hata et al. and Sun et al. still reads on claim 1. Accordingly, the rejection of claims 1-23 still stands.

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within

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TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Joseph Nguyen whose telephone number is (571) 272-1734. The examiner can normally be reached on Monday-Friday, 7:30 am- 4:30 pm. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Thomas can be reached on (571) 272-1664. The fax phone number for the organization where this application or proceeding is assigned is (571) 273-8300 for regular communications.

SOF Kenneth Parla

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

JN March 31, 2006.